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Transport properties and electronic states of anatase Li₂TiO, epitaxial thin films

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Introduction

 $Ti_{1,x}Nb_xO_2$ has been recognized as an excellent transparent conducting oxide with low resistivity and high visible-light transmittance [1]. In this material, each Nb⁵⁺ substituting for Ti⁴⁺ releases one conduction electron, which contributes to the low resistivity. It is thus expected that cations intercalated into anatase lattice will produce carriers. In this study, we have synthesized epitaxial thin films of anatase TiO₂ doped with Li, Li_xTiO₂, by using pulsed laser deposition (PLD) technique, and investigated their transparent conducting properties and electronic structures.

Experiment

Epitaxial thin films of anatase $Li_{0.074}TiO_2$ were grown on $(La_{0.3}Sr_{0.7})(Al_{0.65}Ta_{0.35})O_3$ (100) substrates by PLD. The anatase structures of these films were confirmed by X-ray diffraction. Transport properties [i.e., dc resistivity (ρ), carrier density (n_e), and Hall mobility ($\mu_{\rm H}$)] were characterized based on standard six-terminal geometry under external magnetic field up to 8 T perpendicular to the film surfaces. Valence-band electronic states were measured by soft X-ray photoemission spectroscopy (PES) using BL-2C at the Photon Factory, KEK.

Results and Discussion

Figure 1 plots ρ -*T* curve of Li_{0.074}TiO₂ and Ti_{0.94}Nb_{0.06}O₂ thin films. Notably, the ρ -*T* curves of Li_{0.074}TiO₂ show metallic behavior. The ρ (300 K) is ~1 × 10³ Ωcm, which is approximately five times higher than that of Ti_{0.94}Nb_{0.06}O₂ films (2 × 10⁻⁴ Ωcm). The n_e (300 K) value is as high as 5 × 10²⁰-1 × 10²¹ cm⁻³, being

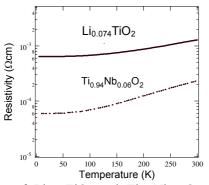


Fig.1: ρ of Li_{0.074}TiO₂ and Ti_{0.94}Nb_{0.06}O₂ films as functions of temperature.

comparable to that of $Ti_{0.94}Nb_{0.06}O_2$. On the other hand, the $\mu_{\rm H}(300 \text{ K})$ value of the $Li_{0.074}TiO_2$ films (10-15 cmV⁻¹S⁻¹) is 1/2 -1/3 of that $Ti_{0.94}Nb_{0.06}O_2$. These results indicate that high ρ of $Li_{0.074}TiO_2$ can be almost due to low $\mu_{\rm H}$.

Figure 2 shows the valence-band spectra of $\text{Li}_{0.074}\text{TiO}_2$ films near the Fermi level ($E_{\rm F}$) obtained by Ti 2*p*-3*d* onand off-resonant PES with a photon energy of hv = 467eV and 453 eV, respectively. Around the binding energy ($E_{\rm B}$) of 0.5-3 eV, in-gap states can be clearly observed. Furthermore, the intensity around $E_{\rm B} = 1-2$ eV are enhanced in a Ti 2*p*-3*d* resonance PES, indicating that the in-gap states have Ti 3*d* orbital nature. On the other hand, there was no state near $E_{\rm F}$ in Li_{0.074}TiO₂ films, although there is a state near $E_{\rm F}$ in the case of Ti_{1-x}Nb_xO₂ [2]. These results suggest that the difference of mechanism of conduction between Li_xTiO₂ and Ti_{1-x}Nb_xO₂ is attributed to the states from each dopants.

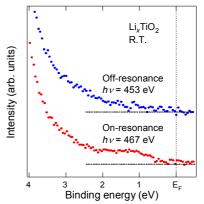


Fig.2: Ti 2*p*-3*d* on- and off-resonant PES of Li_vTiO_2 films obtained with a photon energy of hv = 467 eV and 453 eV, respectively.

References

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